

## EAST Search History

## EAST Search History (Prior Art)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	309701	(siN or silicon nitride or "si.sub.3n.sub.4")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 10:21
S2	2445	S1 and (siN or silicon nitride or "si.sub.3n.sub.4") same (multi-layer or layer) and ("n.sub.2" or nitrogen) with dens\$6	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 10:21
S3	448	S1 and (siN or silicon nitride or "si.sub.3n.sub.4") same (multi-layer or layer) same ("n.sub.2" or nitrogen) with dens\$6	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 10:23
S4	0	S3 and (siN or silicon nitride or "si.sub.3n.sub.4") same (multi-layer) same ("n.sub.2" or nitrogen) with dens\$6	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 10:43
S6	448	S1 and (siN or silicon nitride or "si.sub.3n.sub.4") same (multi-layer or layer) same ("n.sub.2" or nitrogen) with dens\$6	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 10:50
S7	4	S6 and (siN or silicon nitride or "si.sub.3n.sub.4") same (multi-layer) same ("n.sub.2" or nitrogen) with dens\$6	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 10:50
S8	4	S6 and (siN or silicon nitride or "si.sub.3n.sub.4") with (multi-layer) same ("n.sub.2" or nitrogen)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 10:50
S28	7	("2004/0121085").URPN.	USPAT	ADJ	ON	2009/02/25 14:10
S29	309701	(siN or silicon nitride or "si.sub.3n.sub.4")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 14:16
S30	732	S29 and (hot wire or hotwire)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 14:16
S31	257	S30 and (hydrogen or "h.sub.2")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 14:18

S36	310022	(siN or silicon nitride or "si.sub.3n.sub.4")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/26 08:17
S37	254	S36 and (siN or silicon nitride or "si.sub.3n.sub.4") same treat\$4 same repeat\$4	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/26 08:17
S38	84	S37 and (siN or silicon nitride or "si.sub.3n.sub.4") same treat\$4 with repeat\$4	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/26 08:17
S40	328874	(siN or silicon nitride or "si.sub.3n.sub.4")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/09/10 09:18
S41	516	S40 and (siN or silicon nitride or "si.sub.3n.sub.4") same (mult-layer or layer) same ("n.sub.2" or nitrogen) with dens\$6	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/09/10 09:18
S72	2	"20040121085"	US-PGPUB; USPAT	ADJ	ON	2010/01/17 09:47
S88	1	"6689220".pn.	US-PGPUB; USPAT; EPO	ADJ	ON	2010/08/17 09:11
S91	8588	(siN or silicon nitride or "si.sub.3n.sub.4") and ((rectang\$7 with (puls\$4 or flow)) or simultaneous\$4 with (valve or switch\$4))	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2010/08/17 10:04
S92	1964	S91 and ("h.sub.2" or hydrogen)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2010/08/17 10:06
S93	623	S91 and ("h.sub.2" or hydrogen) with (treat\$6 or post-treat\$6 or posttreat\$6 or SIN or silicon nitride or "si.sub.3.n.sub.4")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2010/08/17 10:07
S94	97	S91 and ("h.sub.2" or hydrogen) with (treat\$6 or post-treat\$6 or posttreat\$6 or SIN or silicon nitride or "si.sub.3.n.sub.4") same (dens\$6 or multi-layer or multiple layer)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2010/08/17 10:07
S95	92	S94 and ("427"/\$.ccls. or CVD or vapor deposition)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2010/08/17 10:08
S96	10	S91 and ("h.sub.2" or hydrogen) with (treat\$6 or post-treat\$6 or posttreat\$6) same (SIN or silicon nitride or "si.sub.3.n.sub.4") same (dens\$6 or multi-layer or multiple layer)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2010/08/17 10:09

S97	141	S91 and ("h.sub.2" or hydrogen) with (treat\$6 or post-treat\$6 or posttreat\$6) same (SiN or silicon nitride or "si.sub.3.n.sub.4")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2010/08/17 10:10
S98	164	S91 and ("h.sub.2" or hydrogen) with (treat\$6 or post-treat\$6 or posttreat\$6 or dens\$6) same (SiN or silicon nitride or "si.sub.3.n.sub.4")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2010/08/17 10:10
S99	4	((MAKI KO) near2 (KITAZOE)). INV.	US-PGPUB; USPAT	ADJ	ON	2011/03/30 10:30
S100	1	((HI FOMI) near2 (ITHO)). INV.	US-PGPUB; USPAT	ADJ	ON	2011/03/30 10:30
S101	8	((SHIN) near2 (ASARI)). INV.	US-PGPUB; USPAT	ADJ	ON	2011/03/30 10:30
S102	44	((KAZUYA) near2 (SAITO)). INV.	US-PGPUB; USPAT	ADJ	ON	2011/03/30 10:30
S103	50	S99 or S100 or S101 or S102	US-PGPUB; USPAT	ADJ	ON	2011/03/30 10:30
S104	50	S103	US-PGPUB; USPAT	ADJ	ON	2011/03/30 10:30
S105	385382	(siN or silicon nitride or "si.sub.3n.sub.4")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2011/03/30 10:30
S106	125	S105 and (siN or silicon nitride or "si.sub.3n.sub.4") same (multi-layer or multiple layer) and ("n.sub.2" or nitrogen) with dens\$6	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 10:30
S107	173	S105 and (siN or silicon nitride or "si.sub.3n.sub.4") same (multi-layer or multiple layer) and ("n.sub.2" or nitrogen or nh3 or "nh.sub.3" or ammonia) with dens\$6	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 10:30
S108	32	S107 and (cat-cvd or catalyst)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 10:31
S109	3360	S105 and (siN or silicon nitride or "si.sub.3n.sub.4") same (multi-layer or multiple layer) and ("n.sub.2" or nitrogen or nh3 or "nh.sub.3" or ammonia)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 10:33
S110	402	S109 and (cat-cvd or catalyst)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 10:33

S111	1	"20020104477"	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 10:36
S112	27	S110 and "427"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 10:38
S113	2	"20040121085"	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 10:38
S114	1	"20010012650"	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 10:41
S115	1	"6017784".pn.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 10:43
S116	1045	S109 and (cat-cvd or catalyst or wire or hotwire)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 10:44
S117	41	S116 and "427"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 10:45
S118	385382	(siN or silicon nitride or "si.sub.3n.sub.4")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2011/03/30 12:07
S119	2424	S118 and (siN or silicon nitride or "si.sub.3n.sub.4") same (multi-layer or multiple layer) and ("h.sub.2" or hydrogen)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 12:07
S121	796	S119 and (cat-cvd or catalyst or wire or hotwire)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 12:08
S122	797	S118 and (siN or silicon nitride or "si.sub.3n.sub.4") same (multi-layer or multiple layer) and ("h.sub.2" or hydrogen) same (siN or silicon nitride or "si.sub.3n.sub.4")	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 12:08
S123	199	S122 and (cat-cvd or catalyst or wire or hotwire)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 12:08
S124	199	S122 and (cat-cvd or catalyst or catalytic (CVD or chemical vapor deposition) or wire or hotwire)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 12:09
S125	9	S122 and (cat-cvd or (catalyst or catalytic) (CVD or chemical vapor deposition) or hot wire or hotwire)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 12:10

S126	32	S119 and (cat-cvd or (catalyst or catalytic) (CVD or chemical vapor deposition) or hot wire or hotwire)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 12:10
S127	18241	S118 and (siN or silicon nitride or "si.sub.3n.sub.4") same ("h.sub.2" or hydrogen)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 12:13
S128	189	S127 and (cat-cvd or (catalyst or catalytic) (CVD or chemical vapor deposition) or hot wire or hotwire)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 12:13
S129	69	S128 and (hydrogen or "h.sub.2" or "nh.sub.3" or ammonia) with (treat\$6 or post-treat\$6 or anneal\$4)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 12:13
S130	4	("2002/0086557").URFN.	USPAT	ADJ	ON	2011/03/30 12:19
S131	16	"6069094"	USPAT	ADJ	ON	2011/03/30 12:20
S132	17	"6069094"	US-PGPUB; USPAT	ADJ	ON	2011/03/30 12:20
S133	6	S132 and (hydrogen or "h.sub.2" or "nh.sub.3" or ammonia) with (treat\$6 or post-treat\$6 or anneal\$4)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 12:20
S134	503	(siN or silicon nitride or "si.sub.3n.sub.4") same (remov \$6) adj3 (cl or chlorine or halide or halogen or hydrogen)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2011/03/30 12:33
S135	216	(siN or silicon nitride or "si.sub.3n.sub.4") with (remov \$6) adj3 (cl or chlorine or halide or halogen or hydrogen)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2011/03/30 12:33
S136	188	(siN or silicon nitride or "si.sub.3n.sub.4") with (remov \$6) adj3 ("h.sub.2" or hydrogen)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2011/03/30 12:36
S137	289	(siN or silicon nitride or "si.sub.3n.sub.4") same (cat-cvd or (catalyst or catalytic) (CVD or chemical vapor deposition) or hot wire or hotwire)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2011/03/30 12:38

S138	63	(siN or silicon nitride or "si. sub.3n.sub.4") and (cat-cvd or (catalyst or catalytic) (CVD or chemical vapor deposition) or hot wire or hotwire) and (h or hydrogen) (content or impurity)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2011/03/30 12:39
S139	80	"250438"	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2011/03/30 12:51
S140	2	"6709512".pn.	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2011/03/30 13:06
S141	0	Applied Physics with "66" with "No."	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2011/03/30 13:11
S143	76	Applied Physics with "66" and catalyt\$4	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2011/03/30 13:12
S144	19	8-250438	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2011/03/30 13:20
S145	1	10/593444	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 15:11
S146	89	(HCD or "Si.sub.2cl.sub.6" or hexachlorodisilane) and (cataly\$6 (CVD or chemical vapor) or Cat-CVD or hot-wire)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 15:22
S147	164	(disilane) and (cataly\$6 (CVD or chemical vapor) or Cat-CVD or hot-wire)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 15:25
S148	25	(disilane) same (cataly\$6 (CVD or chemical vapor) or Cat-CVD or hot-wire)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 15:25
S149	741	(silane or "sih.sub.4") and (cataly\$6 (CVD or chemical vapor) or Cat-CVD or hot-wire)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 15:29
S150	636	(silane or "sih.sub.4") and (cataly\$6 (CVD or chemical vapor) or Cat-CVD or hot-wire) and (impur\$6 or hydrogen)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 15:30
S151	69	(silane or "sih.sub.4") and (cataly\$6 (CVD or chemical vapor) or Cat-CVD or hot-wire) and (impur\$6 or hydrogen) (content or level)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 15:30

S152	4227	(silane or "sil.sub.4") and (impur\$6 or hydrogen) (content or level)	US-PGRUB; USPAT; EPO; JPO	ADJ	ON	2011/03/30 16:21
------	------	-----------------------------------------------------------------------------	---------------------------------	-----	----	---------------------

**EAST Search History (Interference)**

&lt; This search history is empty &gt;

**3/ 31/ 2011 7:23:59 AM****C:\ Documents and Settings\ jmillers5\ My Documents\ EAST\ Workspaces\ Old cases\ 10-593444  
unit treatment - RCE.wsp**